



Ecopia Rapid Thermal Processing System



- Heat treatment at low pressure
- Heat treatment at atmospheric pressure
- High accuracy temperature control
- No need for additional cooling system
- Compact desktop design
- Competitively priced

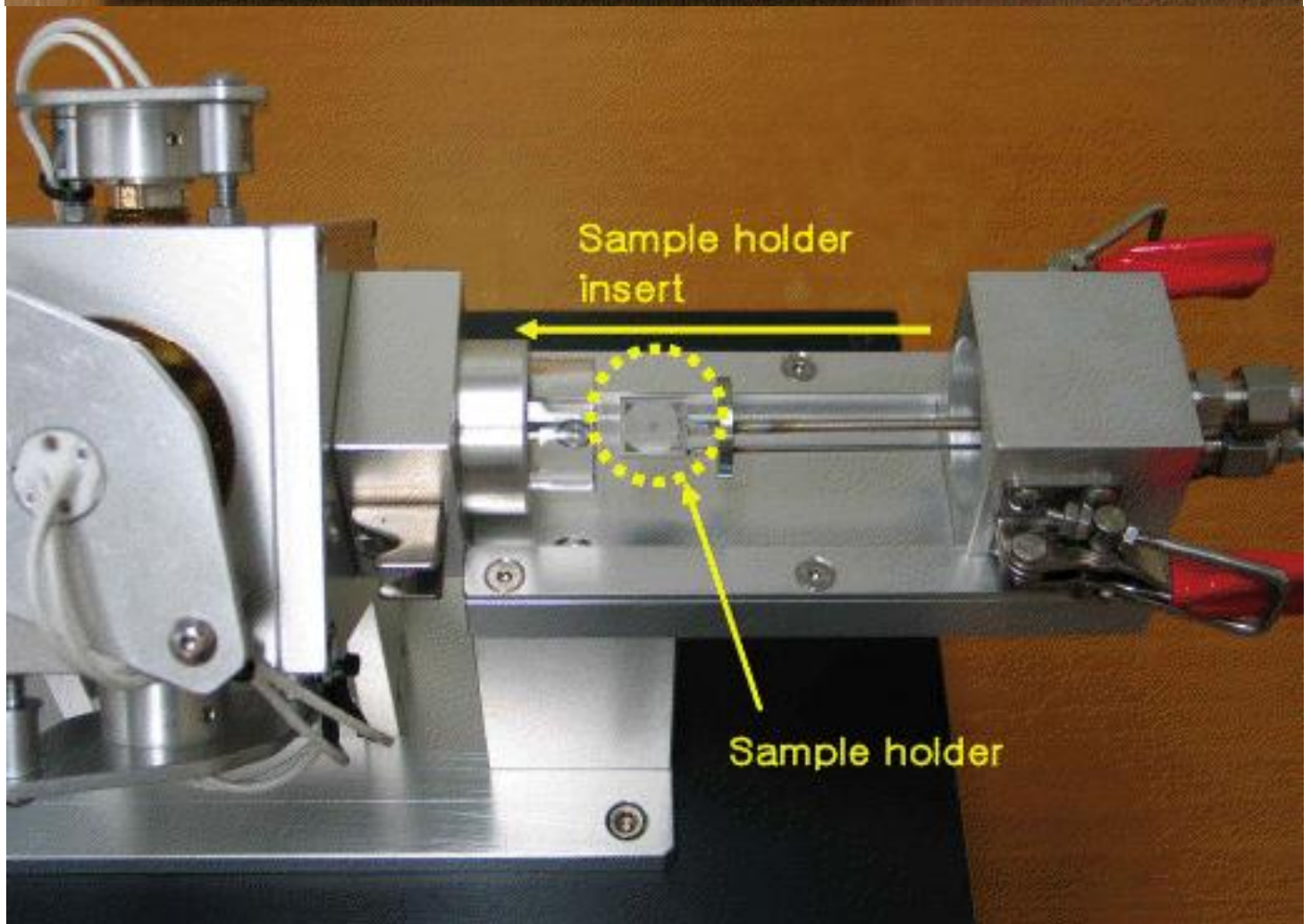
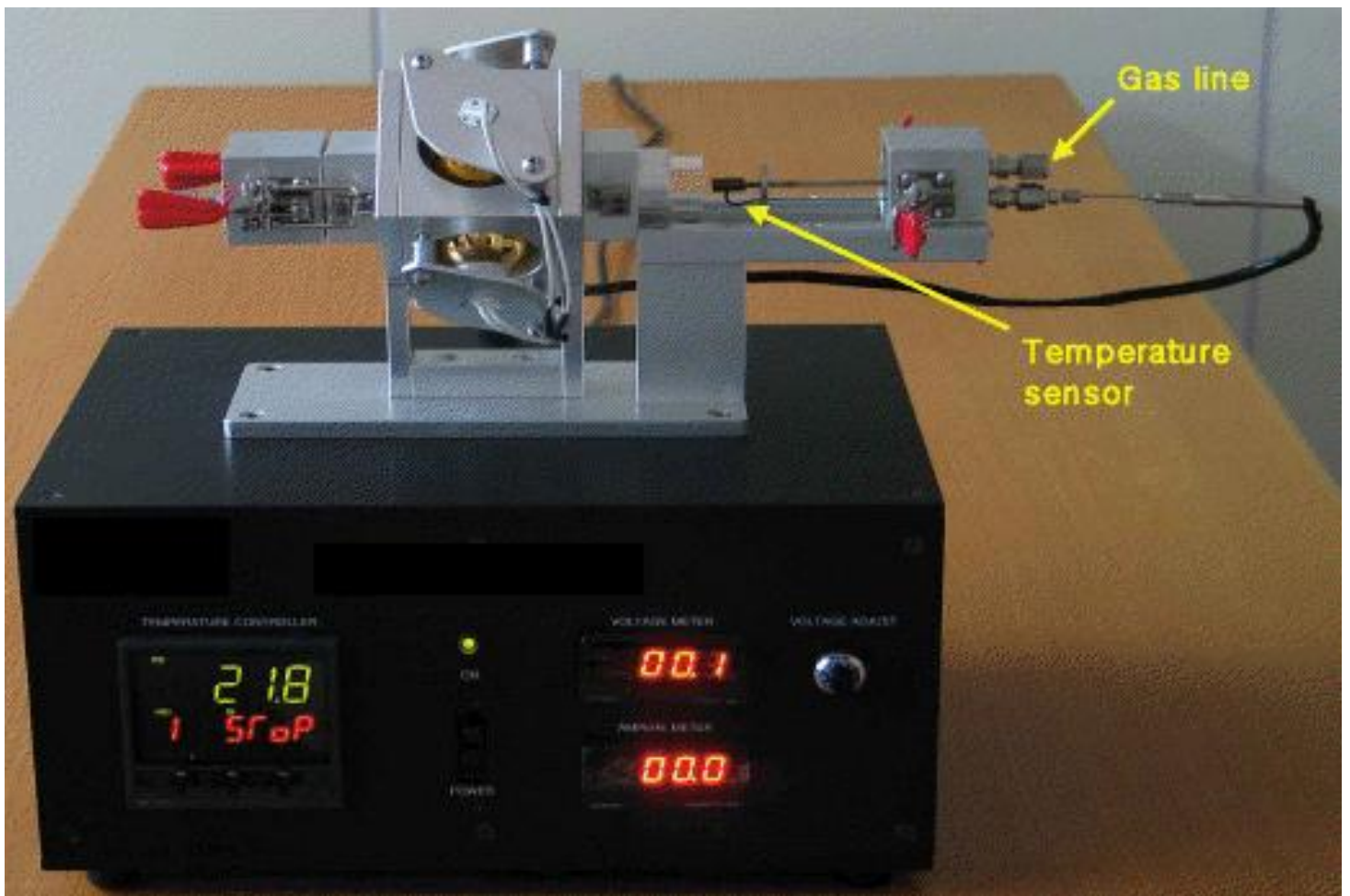
The RTP-1200 model is an easy-to-use yet powerful Rapid Thermal Processing system. Very high temperatures are attained using four tungsten-halogen lamps. The system is easy to install and operate. Valuable test data can be gathered quickly and conveniently at a very reasonable price.

Applications:

- Thin film deposition
- Oxidize thin film on the sample
- Construction analysis of thin film at high temperature
- Paste material analysis
- Ohmic contact formation by .i.e., Ag Au electrical conductivity material
- Heat treatment after ion implantation and activating ion implantation
- Melting point analysis of alloy

Characteristics:

- Easy to operate for heating samples at low pressure, purging gas, bringing sample under vacuum, and using at ambient atmospheric pressure.
- No need for additional cooling system
- Very convenient to load and unload of tested materials
- Compact desktop design and convenient to move and install.
- Accurate temperature control using temperature sensor in sample loading stage
- Can be used as furnace with capability of +/- 3°C accuracy.



SPECIFICATIONS

Maximum Sample Size	15mm x 15mm or 15mm x 20mm
Maximum rate of temperature rise	100°C/second
Maximum cooling rate	1000°C to 400° in 50 seconds
Maximum Temperature	1200°C
Lamp Power	600 Watts
Temperature Accuracy	+/-0.3°C at 1000°C
System Size	40cm x 30cm x 45cm
System Weight	30Kg (66 lbs)
Electrical	220V, single phase
Cooling system	None required